Title (en)

Forming method of patterned coating.

Title (de)

Verfahren zur Herstellung einer gemusterten Beschichtung.

Title (fr)

Méthode de formation d'une couche à dessins.

Publication

EP 0406667 B1 19950111 (EN)

Application

EP 90112121 A 19900626

Priority

- JP 16480789 A 19890627
- JP 33103989 A 19891222

Abstract (en)

[origin: EP0406667A1] The invention relates to a method of forming a patterned coating upon a surface of a substrate (10). A plurality of separated magnetic elements (11) are arranged side by side forming an arrayed module (15) of the elements (11). Then, the model (15) is brought in close vicinity of the reverse side of the substrate (10). And then, magnetic paint containing powdery magnetic material is applied to the surface of the substrate (10) to make a wet film thereon. Finally, the wet film is hardened through a baking or drying. A continuous pattern corresponding to the configuration pattern of the module (15) appears on the surface of the substrate (10). Alternatively, a coated substrate may be introduced into a magnetic field while a wet film of magnetic paint is carried thereon.

IPC 1-7

B44C 1/00; B05D 5/06

IPC 8 full level

B05D 3/14 (2006.01); **B05D 5/06** (2006.01); **B44C 1/04** (2006.01); **H01F 41/16** (2006.01)

CPC (source: EP KR)

B05D 3/203 (2013.01 - EP); **B05D 5/00** (2013.01 - KR); **B05D 5/06** (2013.01 - KR); **B05D 5/061** (2013.01 - EP); **B44C 1/04** (2013.01 - EP); **H01F 41/16** (2013.01 - EP); H01F 7/02 (2013.01 - EP)

Citation (examination)

PATENT ABSTRACTS OF JAPAN, vol.6, no. 73, (C-101)(66) May 8, 1982; JP A 57 010 376 (NITSUSHIN SEIKOU K.K.)

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Designated contracting state (EPC)

DE FR GB NL SE

DOCDB simple family (publication)

EP 0406667 A1 19910109; **EP 0406667 B1 19950111**; AU 5781690 A 19910103; AU 631435 B2 19921126; CA 2019844 A1 19901227; DE 69015900 D1 19950223; DE 69015900 T2 19950622; KR 0135274 B1 19980422; KR 910000250 A 19910129

DOCDB simple family (application)

EP 90112121 A 19900626; AU 5781690 A 19900626; CA 2019844 A 19900626; DE 69015900 T 19900626; KR 900009446 A 19900626